DERWENT- 1979-13525B

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WEEK:

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Prodn. of a porous tantalum plate for an electrolytic capacitor - by adding <u>camphor and naphthalene to tantalum powder</u> and sintering under

vacuum

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PATENT-FAMILY:

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ABSTRACTED-PUB-NO: JP 79001021B

BASIC-ABSTRACT:

Prodn. of a porous Tu plate comprises (a) dissolving 2-7 wt.% (based on <u>Ta powder</u>) <u>camphor</u> in a benzene to form a soln. (I); (b) adding (I) to Ta powder, to form a mixt. (II); (c) mixing (II) with 0.2-2 wt.% (based on Ta powder) napthalene; (d) sintering the final mixt. under vacuum to form a porous Ta plate.

Since the distribution of gaps or spaces among particles of Ta powder is made uniform by adding <u>camphor and naphthalene to Ta powder</u>, the solid electrolytic capacitors produced have low loss, and temp. dependence, of capacitance.

In an example, 5 wt.% <u>camphor</u> is dissolved in benzene and the material is added to Ta powder. 0.5 Wt.% <u>naphthalene</u> is then added to the TA powder. The materials are mixed in a ball mill for a long time and the mixt. is moulded. The moulded plate is heated at 200-300 degrees C at 10-3 - 10-7 Torr to completely evaporate the <u>camphor and naphthalene</u>. The plate is then sintered at 1800-2400 degrees C to provide a Ta plate.

DERWENT-CLASS: E14 E15 L03 M22 V01 X12

CPI-CODES: E10-F02A; E10-J02B4; L03-B03A; M22-H; M22-H03G;